Appendix A

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Tardisare verification status



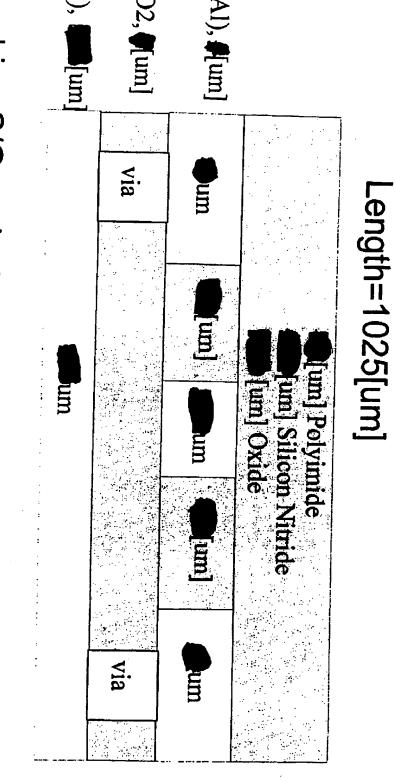
- Studied geometries
- Measurement setup
- EM solver calculation procedure IBM T-line model simulation

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- SiGe technology statistical variation
- Alpha version (January 2001) model vs. measurement Measurement results and EM solver correlation
- Summary & conclusions Beta version (August 2001) model vs. measurement



Single ~50 Ohm Transmission I Sample No.

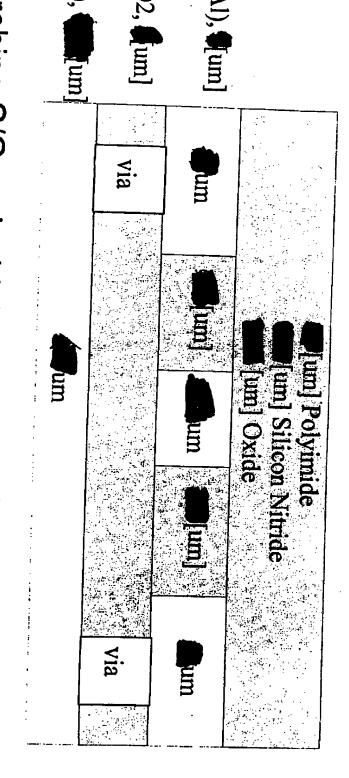


probing S/G pad: shielded AM/MT 30[um]X50[um] Vias present only at both ends of T-line



Sample No. 2

Single ~50 Ohm Transmission Line _ength=4010[um]

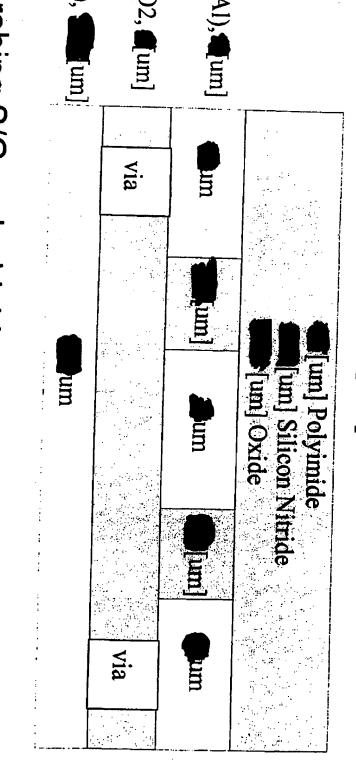


probing S/G pad: shielded AM/MT 30[um]X50[um] Vias present only at both ends of T-line



Sample No. 3

Single ~25 Ohm Transmission Line Length=4010[um]



probing S/G pad: shielded AM/MT 30[um]X50[um] Vias present only at both ends of T-line



Tardware measurement

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- Vector Network Analyzer Two port measurement by 8510C Agilent 40[GHz]
- Standard 40[GHz] RF coaxial cables.
- Wafer probes: structure, beryllium copper tips (properly cleaned) coplanar probes, GSG
- Calibration procedure
- LRRM type, using WinCal software.
- Cascade standard Alumina calibration substrate
- On chip de-embedding by open pad structure, and Y-Parameter subtraction.
- Calibration error: residual tip inductance ~ 10[pH] capacitance ~5[fF]. contact resistance ~ 0.1[Ohm], residual pad



The solver calculation procedure

- Start from Ansoft SI2D quasistatic 2D solver
- Impedance mode calculates EM fields inside the (cross sectional dimensions are ~ 0.1% of 40[GHz] equivalent wavelength)
- metals (full eddy current solution).
- Verify asymptotic inductance values (Linfinity) from basic physics relations. Verify RLC static limits accuracy using Ansoft EM2D
- S Parameters data Perform mathematical conversion to 50[Ohm] based
- Verified against HFSS (with solve in metal option). with HFSS at the low frequency range. Zero order interpolation (and patience...) is required



IBM T-line models were simulated in DE TIPO POQUE SINUATOR

- Simulation in S-Parameter mode environment using the SPECTRES simulator
- Two port simulation, with ideal 50[Ohm] ports
- 1 S-parameter data exported directly from SPECTRES and plotted versus the measured data. For the 4[mm] lines, four 1[mm] T-line models were connected in cascade





technology statistical

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Based on SiGe Design Manual data:

- ~±10% error in T-line capacitance and T-line Metal Line width, Metal line thickness, and SiO₂ inductance values (chip to chip variation). dielectric thickness combined variations lead to
- Same reasons lead to ~±10% error in T-line impedance values (chip to chip).
- T-line resistance variation is ~±20% (chip to chip)

